

	Hits	Search Text	DBs
10	18	((etch\$4 or RIE) same (reduc\$4 or decreas\$5) same (size or width or thickness) same ((top near6 surface) or (top near9 portion)) same (resist or photoresist) same pattern) and ((RIE or etch\$4) near16 (sidewall or side or lateral) near16 (resist or photoresist) near14 pattern)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
11	2	((etch\$4 or RIE) same (reduc\$4 or decreas\$5) same (size or width or thickness) same (((top or upper) near9 (portion or surface or area or side)) or top) same (resist or photoresist) same pattern) and ((RIE or etch\$4) near16 (sidewall or side or lateral or trim\$4) near16 (resist or photoresist) near14 pattern) and ("SO.sub.2")	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
12	6	((etch\$4 or RIE) same (((top or upper) near9 (portion or surface or area or side)) or top) same (resist or photoresist) same pattern) and ((RIE or etch\$4) near16 (sidewall or side or lateral or trim\$4) near16 (resist or photoresist) near14 pattern) and ("SO.sub.2")	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
13	6	((RIE or etch\$4) near16 (trim\$4) near16 (resist or photoresist) near14 pattern) and ("SO.sub.2")	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
14	8	((etch\$4 or RIE) same (((top or upper) near9 (portion or surface or area or side)) or top) same (resist or photoresist) same pattern) and ((RIE or etch\$4) near16 (sidewall or side or lateral or trim\$4) near16 (resist or photoresist) near14 pattern) and ("SO.sub.2" or (sulfur near6 \$3oxide))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
15	2	((etch\$4 or RIE) same (((top or upper) near9 (portion or surface or area or side)) or top) same trim\$4 same (resist or photoresist) same pattern) and ("SO.sub.2" or (sulfur near6 \$3oxide))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
16	0	((etch\$4 or RIE) same (reduc\$4 or decreas\$5) same (size or width or thickness) same ((top near6 surface) or (top near9 portion)) same (resist or photoresist) same pattern) and ((RIE or etch\$4) near16 (sidewall or side or lateral or trim\$4) same (resist or photoresist) same pattern) and "SO.sub.2"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
17	9	((etch\$4 or RIE or trim\$4) same (((top or upper) near9 (portion or surface or area or side)) or top) same (resist or photoresist) same pattern) and ((RIE or etch\$4 or trim\$4) near16 (sidewall or side or lateral or trim\$4) near16 (resist or photoresist) near14 pattern) and ("SO.sub.2" or (sulfur near6 \$3oxide))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
18	24	((etch\$4 or RIE or trim\$4) same (((top or upper) near9 (portion or surface or area or side)) or top) same (resist or photoresist) same pattern) and ((RIE or etch\$4 or trim\$4) near16 (sidewall or side or lateral or trim\$4) same (resist or photoresist) same pattern) and ("SO.sub.2" or (sulfur near6 \$3oxide))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB